

## Resist Compositions with Polymers having 2-Cyano Acrylic Monomer

### Cross Reference to Related Applications

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Related applications are: US Patent Application Serial No. 09/266,342, filed March 11, 1999, now ~~US Patent 6,124,074~~, titled "Photoresist Compositions with Cyclic Olefin Polymers and Additive"; US Patent Application Serial No. 09/266,343, filed March 11, 1999, now ~~US Patent 6,124,074~~, titled "Photoresist Compositions with Cyclic Olefin Polymers and Hydrophobic Non-Steroidal Alicyclic Additives"; US Patent Application Serial No. 09/266,341, filed March 11, 1999, now US Patent 6,124,074, titled "Photoresist Compositions with Cyclic Olefin Polymers and Hydrophobic Non-Steroidal Multi-Alicyclic Additives"; and  
10 US Patent Application Serial No. 09/266,344, filed March 11, 1999, now ~~US Patent 6,124,074~~ titled "Photoresist Compositions with Cyclic Olefin Polymers and Saturated Steroid Additives". Additional related applications are: US Patent Application Serial No. 09/566,395, filed May 5, 2000, now 6,251,560, titled  
15 "Photoresist Compositions with Cyclic Olefin Polymers Having Lactone Moiety"; US Patent Application Serial No. 09/566,397, filed May 5, 2000, now 6,391,521, titled "Copolymer Photoresist with Improved Etch Resistance"; US Patent Application Serial No. 09/639,784, filed August 16, 2000, now 6,391,521, titled "Resist Compositions Containing Bulky Anhydride Additives"; and US  
20 Patent Application Serial No. 09/639,784, filed August 16, 2000, now 6,391,521 titled "Resist Compositions Containing Lactone Additives." The disclosures of the above applications are incorporated herein by reference.

### Background of the Invention

25 In the microelectronics industry as well as in other industries involving construction of microscopic structures (e.g. micromachines, magnetoresistive heads, etc.), there is a continued desire to reduce the size of structural features. In the microelectronics industry, the desire is to reduce the size of